

ABTRACT OF THE DISCLOSURE**METHOD AND APPARATUS FOR PROCESSING SEMICONDUCTOR SUBSTRATES**

Apparatus and methods for producing semiconductor devices are disclosed. A processing chamber includes an interior component having a stepped region including a plurality of raised sections and recessed sections divided by steps. With this apparatus, it is possible to prevent a film of deposited material formed on the stepped region from peeling, thereby decreasing the number of particles in the chamber and increasing the operation rate.

Fig. 2